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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/658,126		09/08/2003	Julin Wan	02307Z-132710US	02307Z-132710US 9694 EXAMINER	
20350	7590	08/12/2005		EXAM		
		TOWNSEND AND	LOPEZ, CARLOS N			
EIGHTH FLOOR SAN FRANCISCO, CA 94111-3834				. ART UNIT	PAPER NUMBER	
				1731		

DATE MAILED: 08/12/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	
	10/658,126	WAN ET AL.	
Office Action Summary	Examiner	Art Unit	
	Carlos Lopez	1731	
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet w	ith the correspondence add	ress
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a re- If NO period for reply is specified above, the maximum statutory perions - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the main earned patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a cepty within the statutory minimum of third will apply and will expire SIX (6) MON ute, cause the application to become Al	reply be timely filed ty (30) days will be considered timely. VTHS from the mailing date of this com BANDONED (35 U.S.C. § 133).	nmunication.
Status			
1) Responsive to communication(s) filed on 06	June 2005.		
· · · · · · · · · · · · · · · · · · ·	nis action is non-final:		
3) Since this application is in condition for allow closed in accordance with the practice under			merits is
Disposition of Claims			
4) ☐ Claim(s) 1-40 is/are pending in the application 4a) Of the above claim(s) 21-40 is/are withdrest 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-20 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and Application Papers	awn from consideration.		
9) The specification is objected to by the Exami			
10) The drawing(s) filed on is/are: a) a			
Applicant may not request that any objection to the			. 4 4047-1
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the	,	• • •	, ,
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure	nts have been received. nts have been received in A iority documents have been eau (PCT Rule 17.2(a)).	pplication No received in this National S	tage
* See the attached detailed Office action for a lis	st of the certified copies not	received.	
Attachment(s)	_		
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948)		Summary (PTO-413) s)/Mail Date	
Notice of Draftsperson's Patent Drawing Neview (P10-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0 Paper No(s)/Mail Date		nformal Patent Application (PTO-1	152)

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DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-20 are rejected under 35 U.S.C. 102(a) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Wan et al (Silicon Nitride-silicon Carbide Nancocomposites Fabricated by Electric-Field-Assisted Sintering). Wan et al discloses a method of making a dense silicon nitride and silicon carbide crystals. The method comprises activating a 200mesh (75 microns) powder of amorphous silicon nitride and silicone carbide by high-energy ball milling the powder (See Experimental Procedures). The activated powder is then sintered, deemed as the claimed consolidation step, by a plasma sintering system, electric-field-assisted sintering, which by definition passes an electric current through the powder mixture.

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Wan et al is silent disclosing the size of the powder after is activated by ball milling. However, in view that the powder already passes through a 75 micron sieve it is deemed as inherent or alternatively as obvious to a person of ordinary skill in the art to have particles within the claimed size range of 1 to 100 nanometers. Moreover, due to the ball milling of the 200 meshed powder, particles having 75 microns or less, the ball milling step done in activating the powder would further reduce the particle diameters and thus it would be inherent or at the least obvious to a person of ordinary skill in the art to have particles within the claimed range of 1 to 100 nanometers.

Additionally, Wan notes that composites with grain size well below 100nm can be achieved if the amount of yttria, a metal oxide densification aid, is less than 3% (See last paragraph of the left column in page 526). Hence, the claimed invention of having crystalline grains less than 100nm is clearly taught by Wan by using a metal oxide densification aid of less than 3%, which would encompass applicant's claimed range of at most 1%.

In regards to claims 2-6, Wan et al as noted above envisage the claimed parameters.

As for claims 7-8, the silicone carbon and nitrogen content is 28%, 43%, and 22% based on the nominal formula noted in the first paragraph of the right column in page 526.

As for claims 9-10; the claimed silazane pyrolized in nitrogen, an inert atmosphere, is disclosed in the first paragraph of the right column in page 526.

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As for claims 11-14, the claimed pressure, current and temperature is disclosed in the first paragraph of the right column in page 526.

As for claims 16-17, in view that the claimed steps a and b are performed by Wan et al, it would be inherent or expected that the particles would have the claimed densities.

As for claim 18, see above.

As for claims 19-20, the balling milling is done with silicone nitride balls. The claimed impact rate and charge ratio are obvious process parameters adjusted to obtain the desired particle size and process time.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Carlos Lopez whose telephone number is 571.272.1193. The examiner can normally be reached on Mon.-Fri. 8am - 5pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Steven Griffin can be reached on 571.272.1189. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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